



Optimization of Capillary Z-pinch Discharge Light Source for Lithography

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◆ Development of high power EUV source

● Increase of EUV output power

?EUV power = $\eta_{\text{generator}} \cdot \eta_{\text{coupling}} \cdot \eta_{\text{plasma}} \cdot T \times (\text{Input energy/shot}) \times \text{Rep-rate}$

?Improvement of energy conversion efficiency → Plasma physics

?High repetition rate → All solid-state power system and water cooling

◆ Development of high quality EUV source

● Stability

?Pre-ionization → Optimum condition

● Debris generation

?Minimum input energy → Improvement of energy conversion efficiency

● Debris mitigation

?Gas curtain



◆ Development of high power EUV source

- Relation between current risetime and plasma property & η_{coupling}
- Relation between input energy/shot and debris generation
- Power measurements with EUV calorimeter

◆ New electrode

- Z-pinch without surface discharge
- Separated pre-ionization circuit design

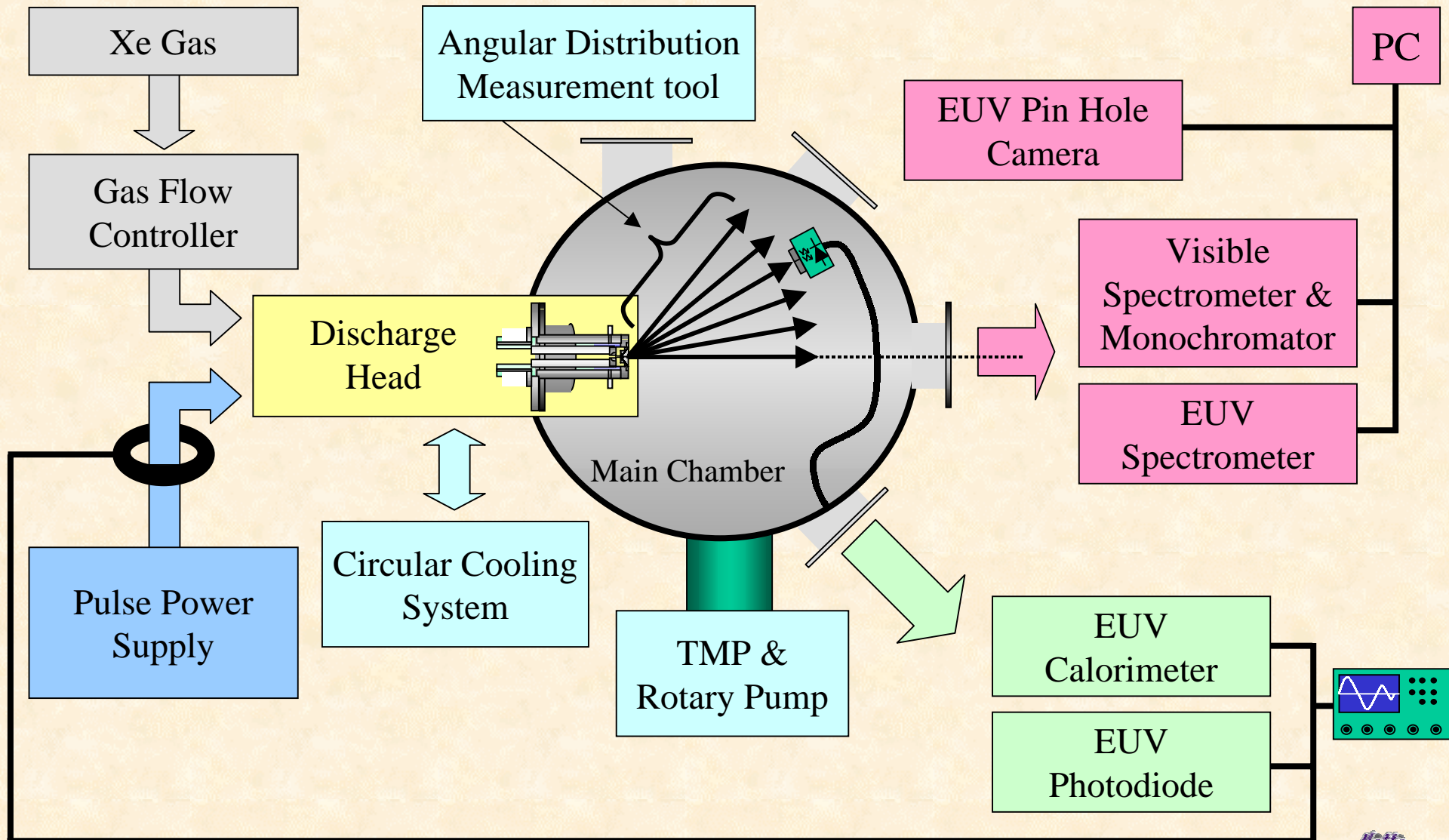
→ Optimum conditions such as plasma property, stability and EUV power

◆ Debris mitigation

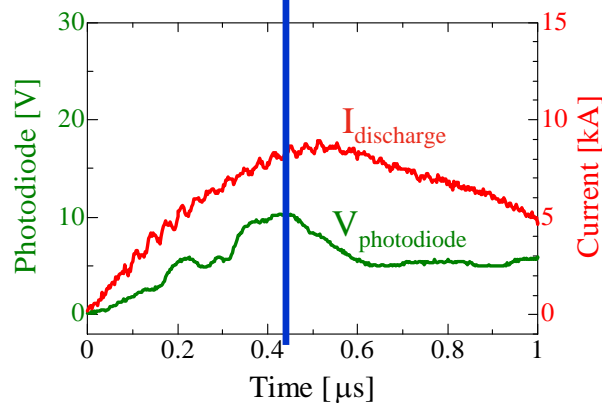
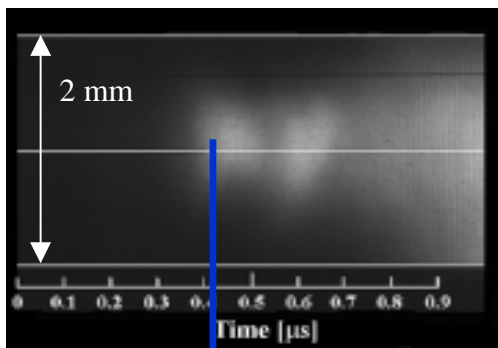
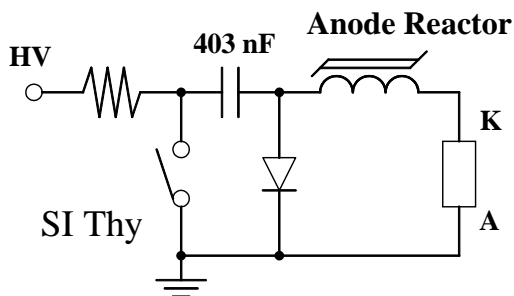
- Design and test setup of gas curtain



Block diagram of experimental system



Direct pulse method



Current dI/dt

500 ns \longrightarrow 160 ns

Pulse width

2.3 μ s \longrightarrow 320 ns

Input energy (/shot)

5.6 J \longrightarrow 4.7 J



Comp. ratio (r_0/r_{min})

2.8 \longrightarrow 9.1

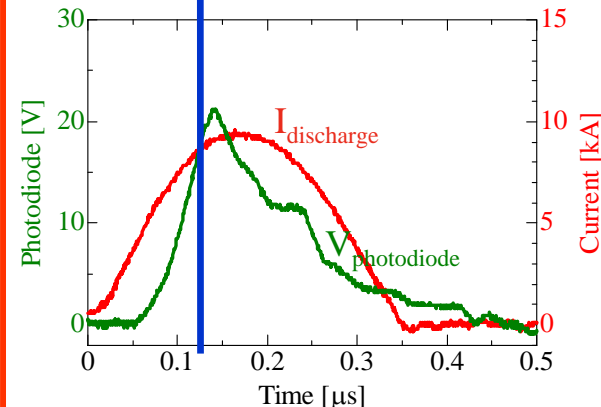
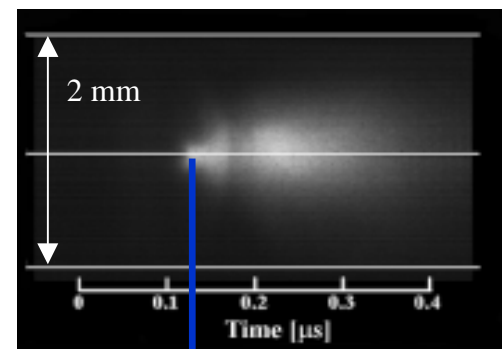
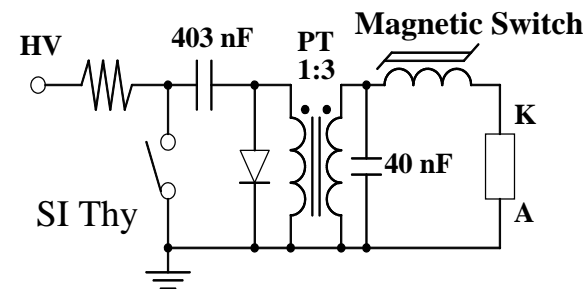
Peak of photodiode signal

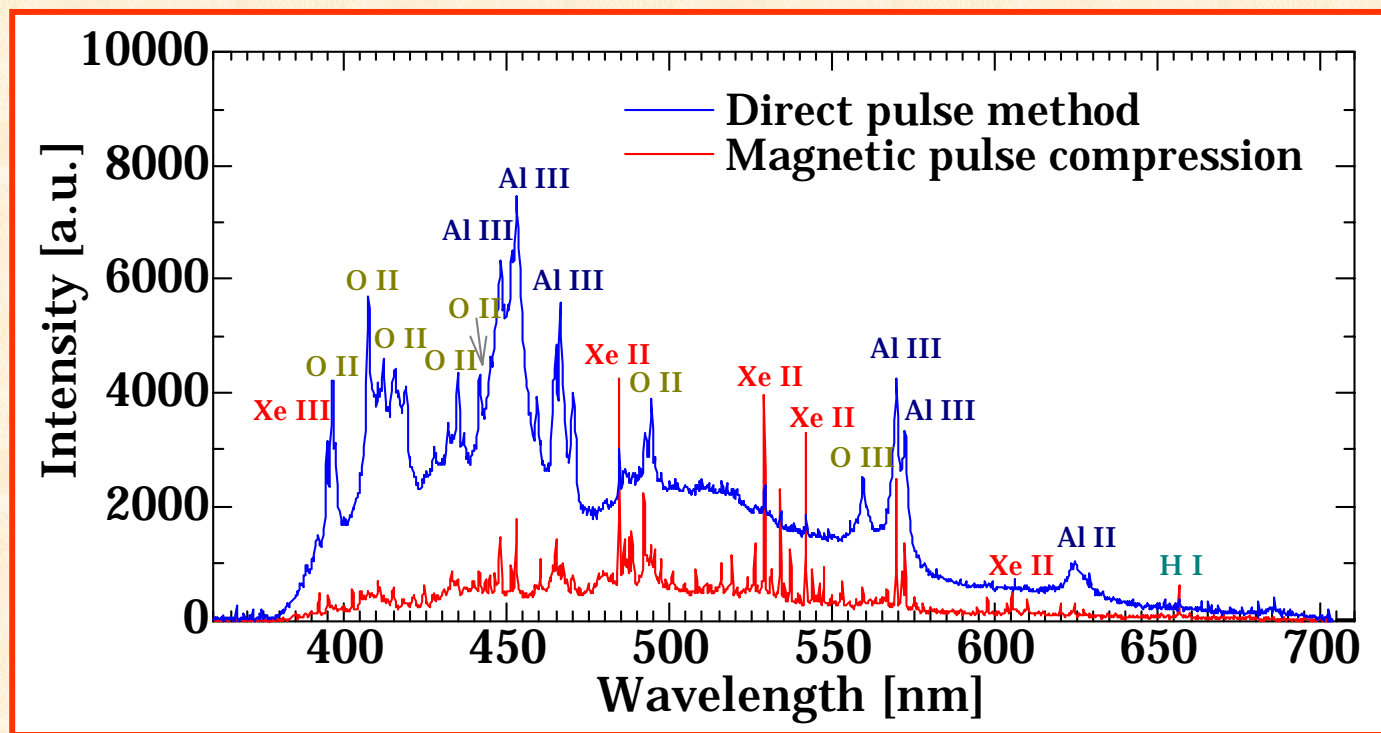
10 V \longrightarrow 22 V

V \cdot sec of photodiode signal

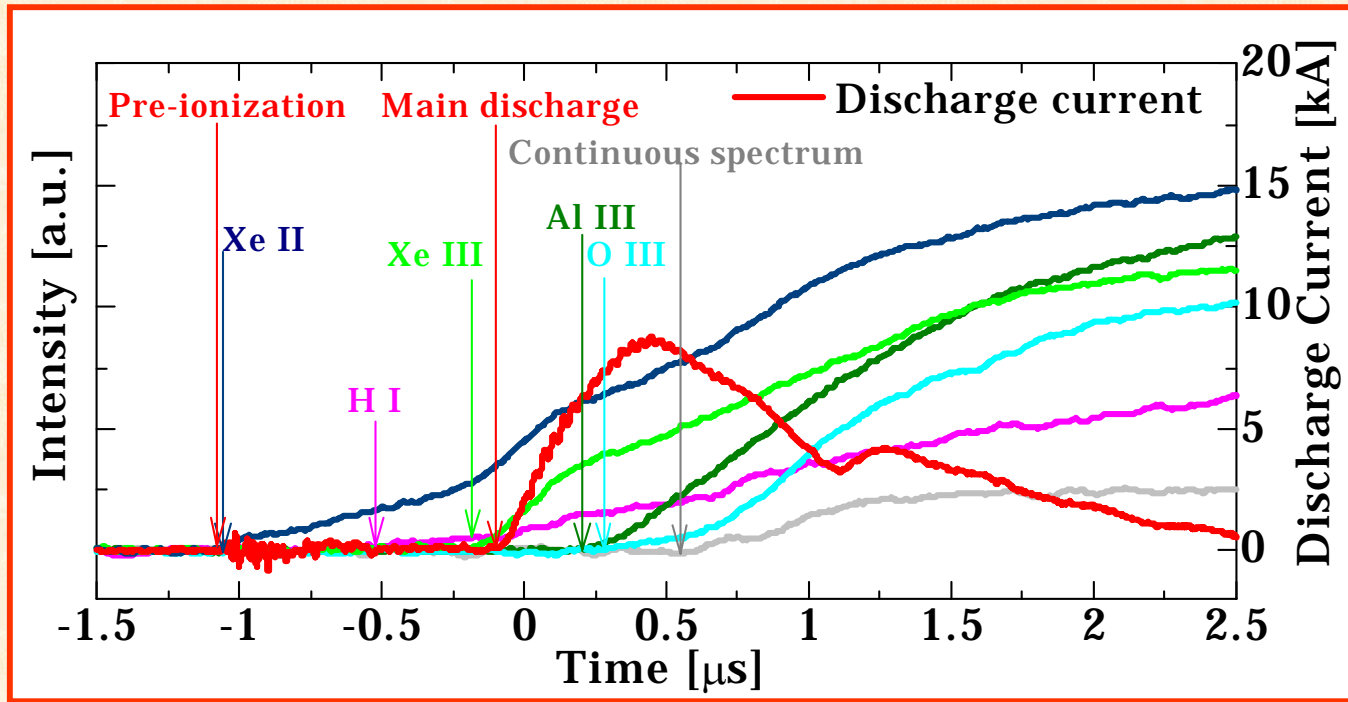
2.27×10^{-8} \longrightarrow 3.28×10^{-9}

Magnetic pulse compression



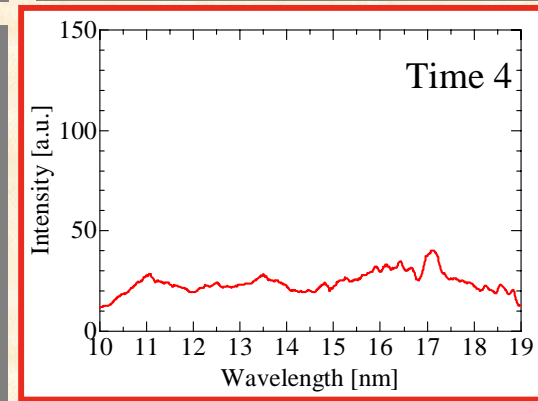
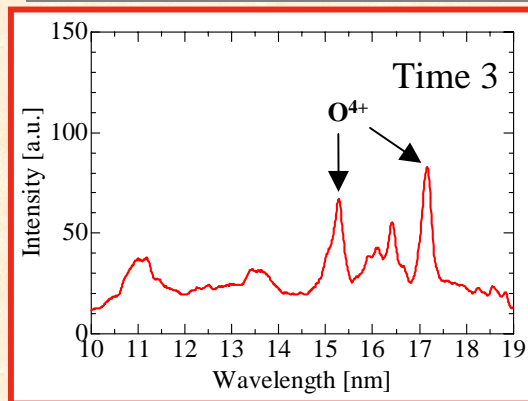
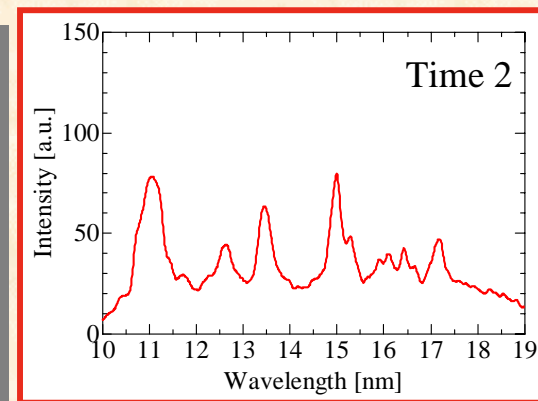
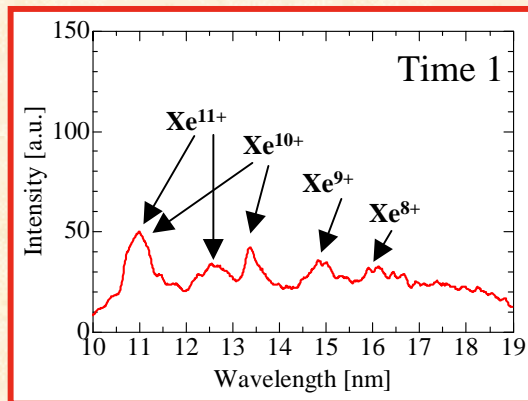
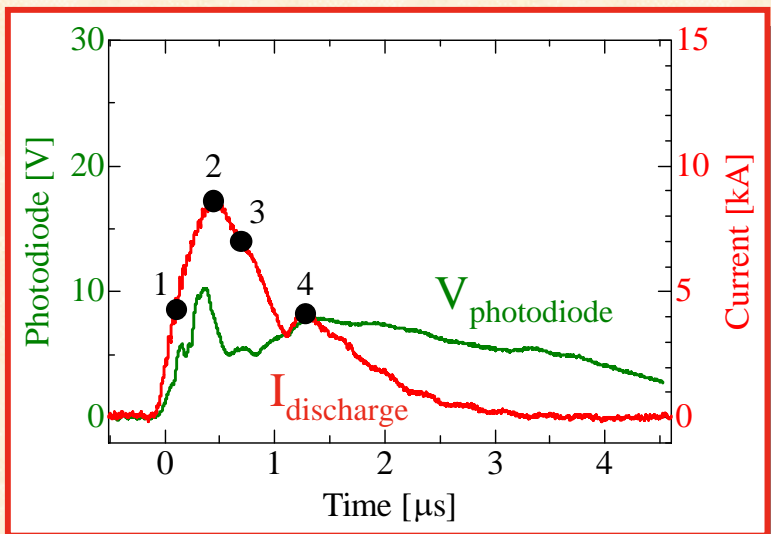


- ◆ Visible emission lines are identified in the each pulse system of plasma
- ◆ Impurities O and Al in direct pulse method come mostly from the capillary
- ◆ Contact time between plasma and capillary in magnetic pulse compression is short enough to prevent impurities from being ablated

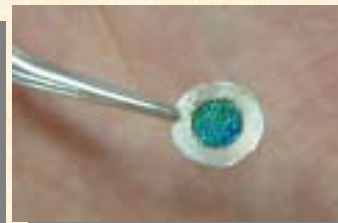
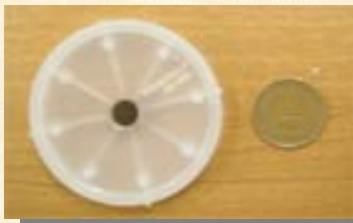
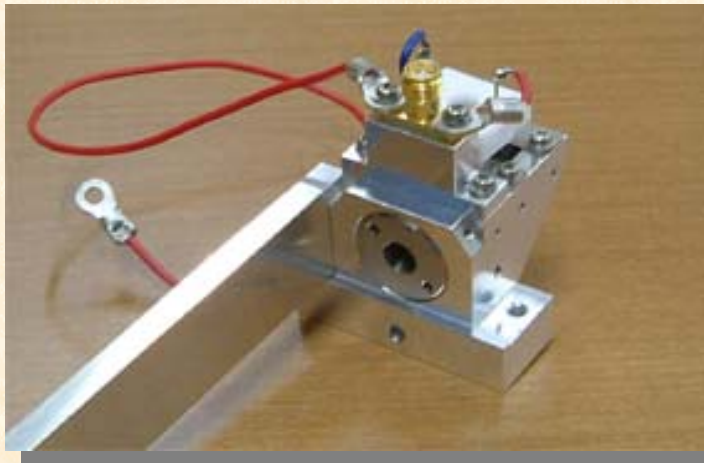
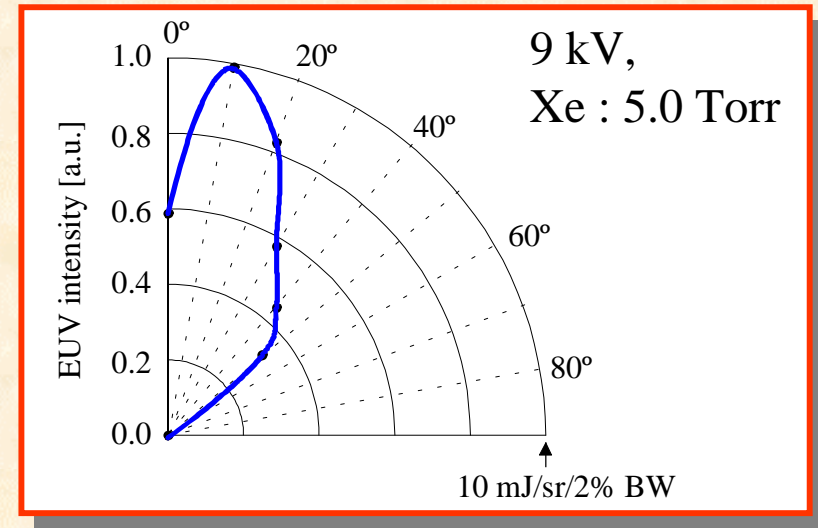
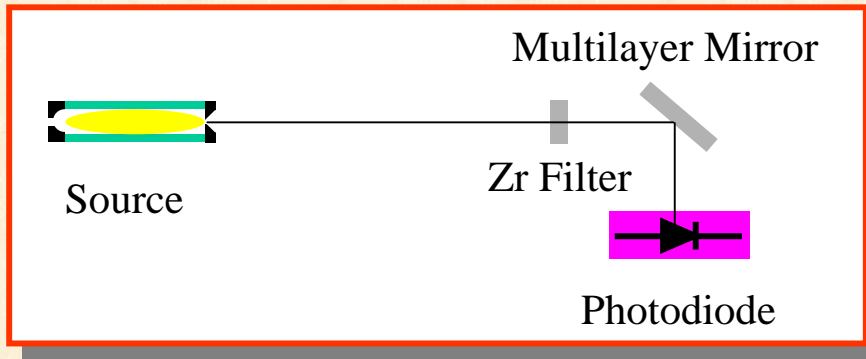


- ◆ Showing the beginning of emission of specific impurity lines
- ◆ Contact of plasma and capillary causes such impurities
- ◆ For magnetic pulse compression, the beginning point of impurity lines compared with discharge current and a kind of impurities are same, but the intensity of impurities is much lower

Gated images recorded at the times indicated on the current pulse



- ◆ Time-resolved analysis is conducted by using the grating incidence monochromator with 600 g/mm MCP, which is gated by an 130 ns, 600V high voltage pulse
- ◆ After the discharge current peak, O impurity lines dominate
- ◆ High dI/dt and short pulse width discharge current is preferable

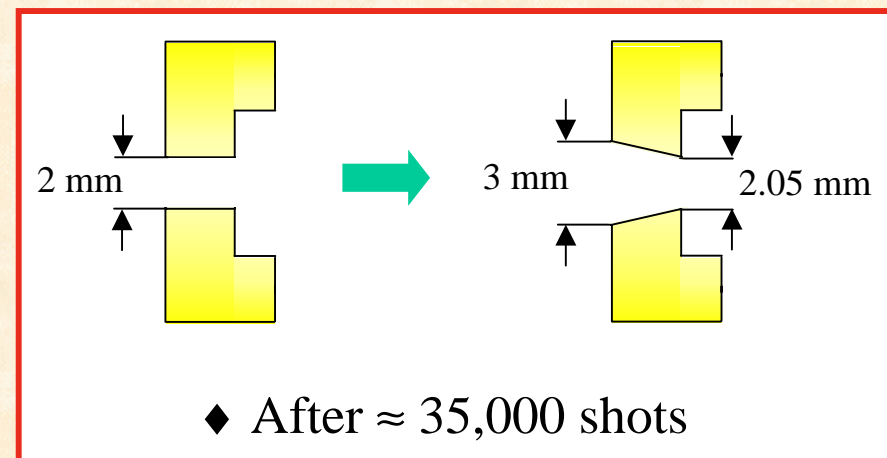
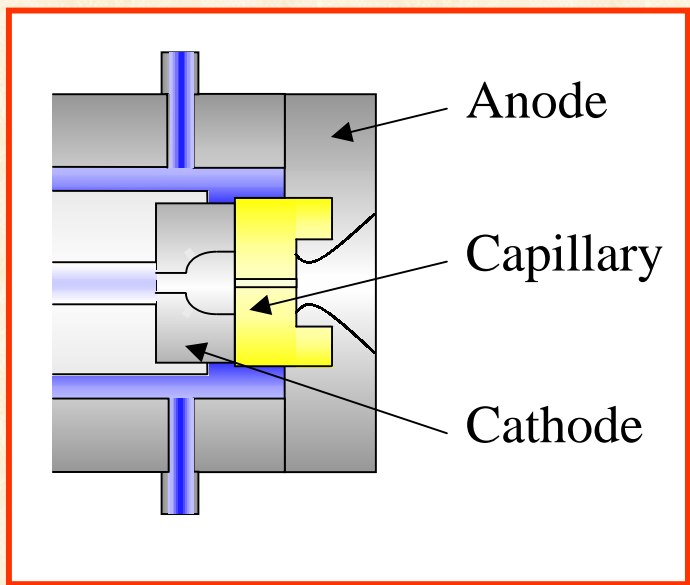


Multilayer Mirror

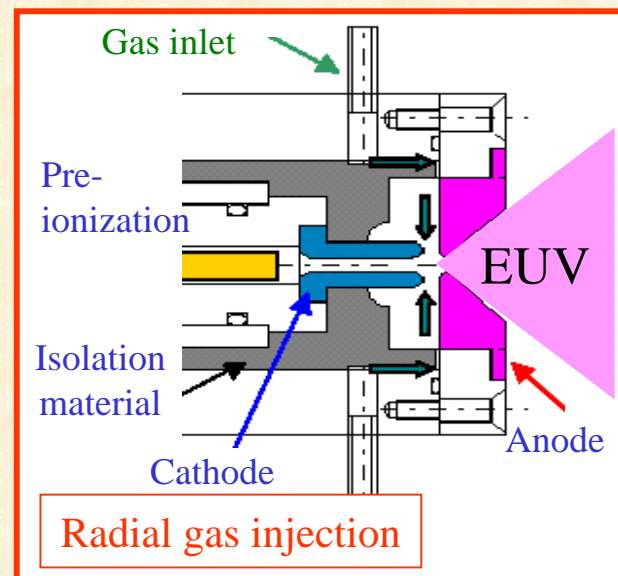
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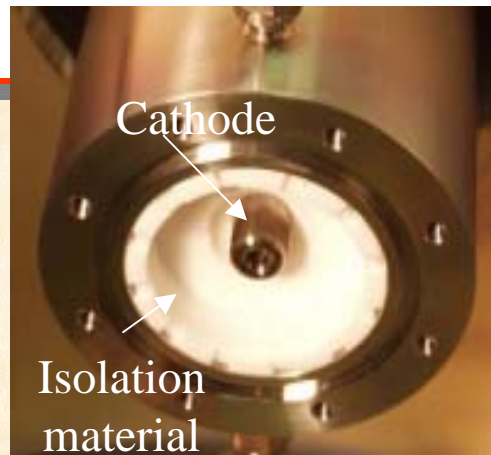
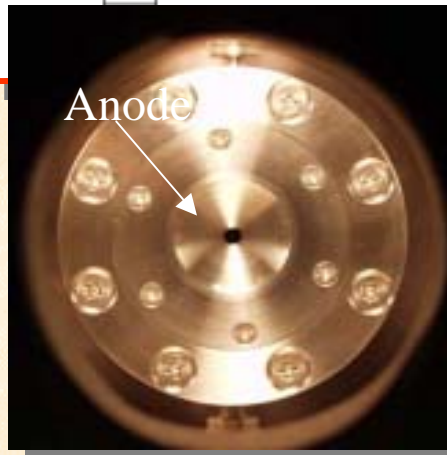
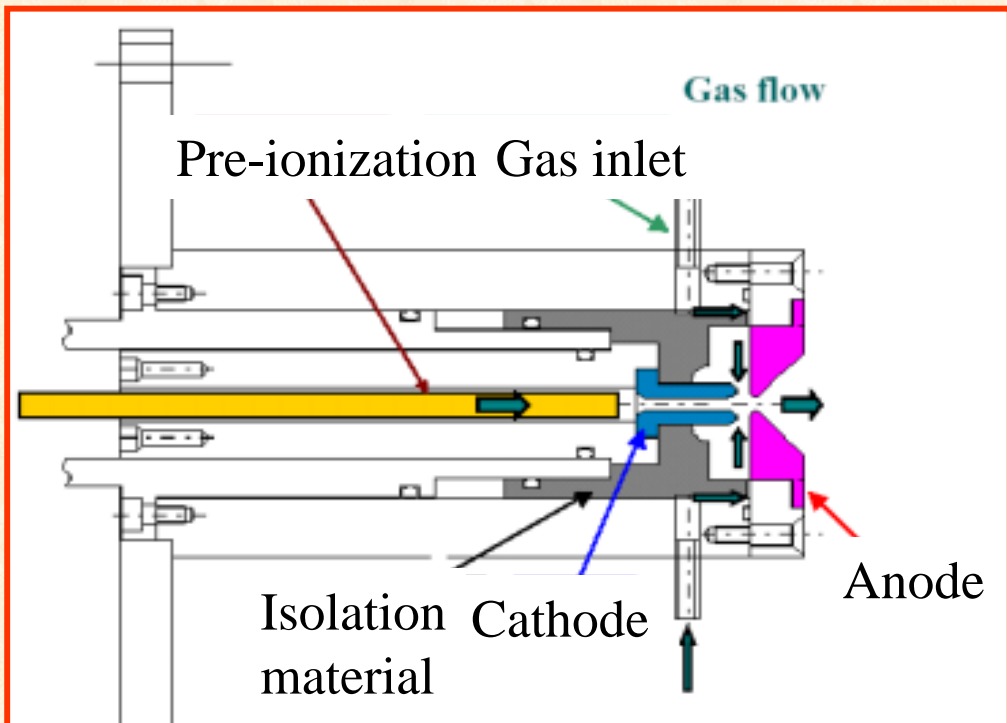
Parylene(0.1 μm)+Zr(0.2 μm)

- ◆ EUV output energy
= 9.9 mJ/sr/2% BW/pulse
- ◆ Effective solid angle (Xe = 5.0 Torr)
 $\rightarrow \Omega_{eff} = 1.74 \text{ sr}$
- ◆ EUV energy at the source (2 % BW)
= 17.2 mJ/pulse
- ◆ EUV conversion efficiency
= 0.24 %/pulse (Will be improved)



- ♦ Inner diameter of cathode side capillary was changed from 2mm to 3mm because of erosion
- ♦ Study of the capillary material
- ♦ Study of the structure of electrode and capillary
- ♦ New discharge concept
→ Designed new discharge head



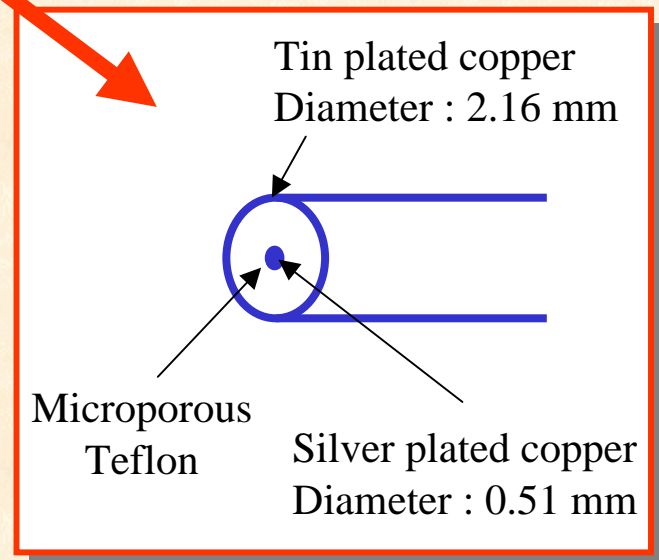
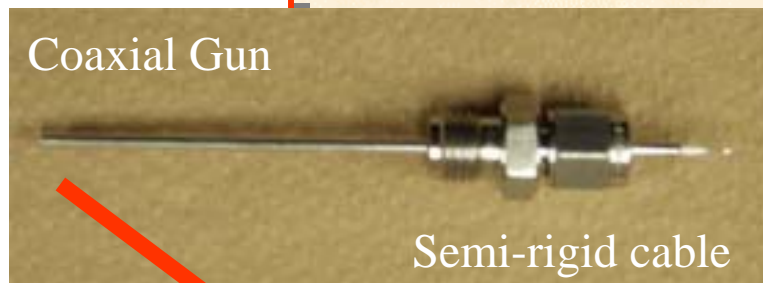
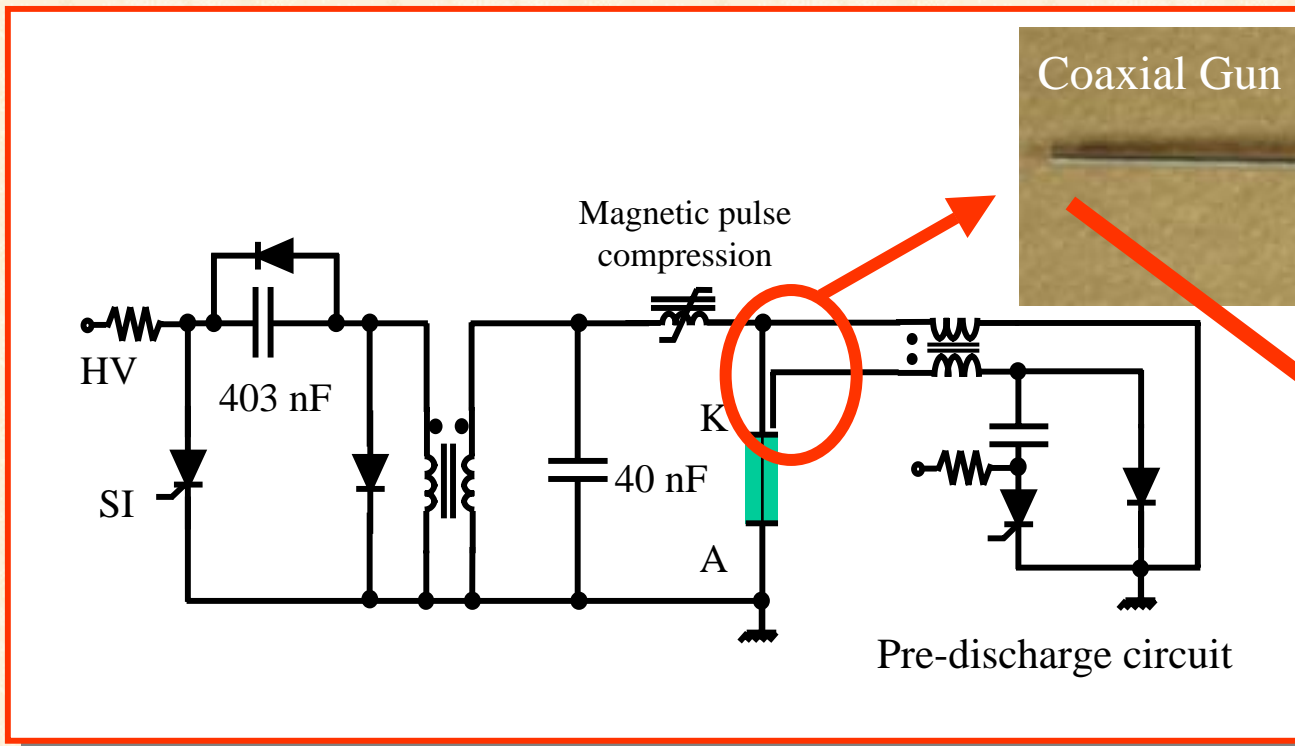


◆ Electrode

- Anode → Mo, inner radius : 4.2 mm
- Cathode → Mo, inner radius : 4 mm
- Insulation material → Teflon

◆ Characteristics

- Z-pinch without surface discharge
- Plasma is isolated from insulation material
- Xe gas is supplied from axial and radial inlet
- Isolated pre-ionization circuit



- ◆ Applying separated pre-ionization circuit
 - Confirm the plasma stability and EUV output

- ◆ Coaxial Gun

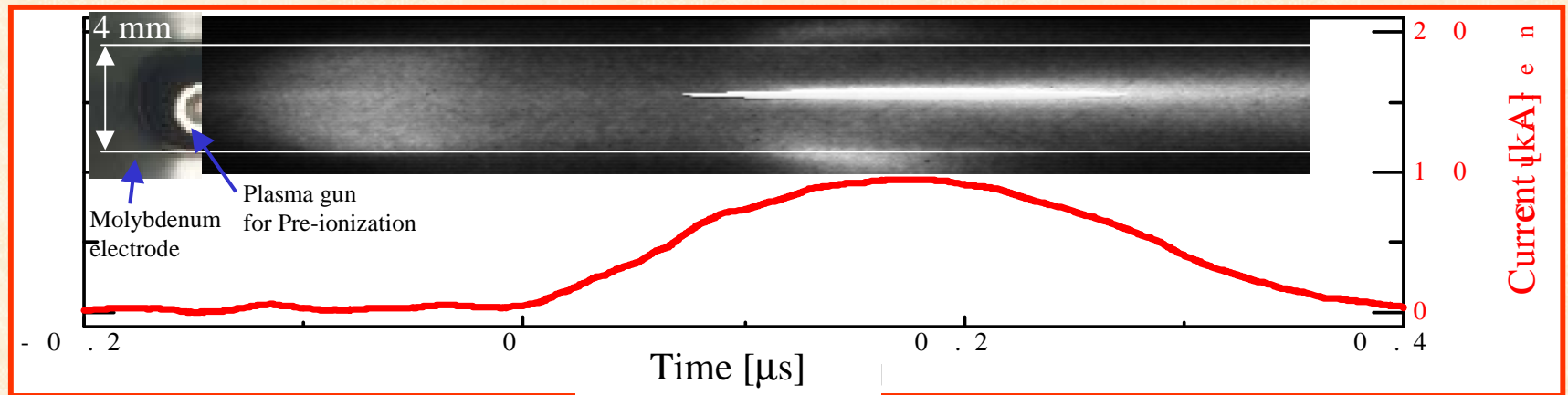
→ Use semi-rigid cable

; Microporous teflon, outer radius : 2.16 mm, inner conductor : 0.51 mm



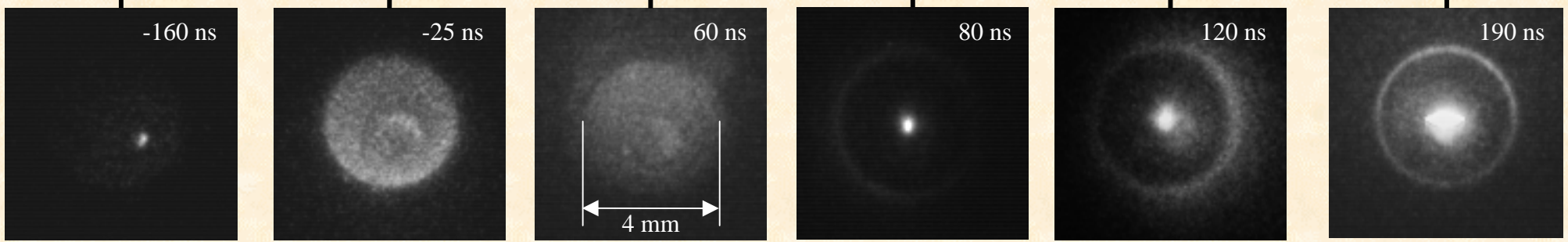
Observation with high speed camera - Z-pinch without surface discharge

Streak



Framing

$V_c = 9 \text{ kV}$, $P = 4 \text{ Torr Xe}$



Pre-ionization by coaxial gun

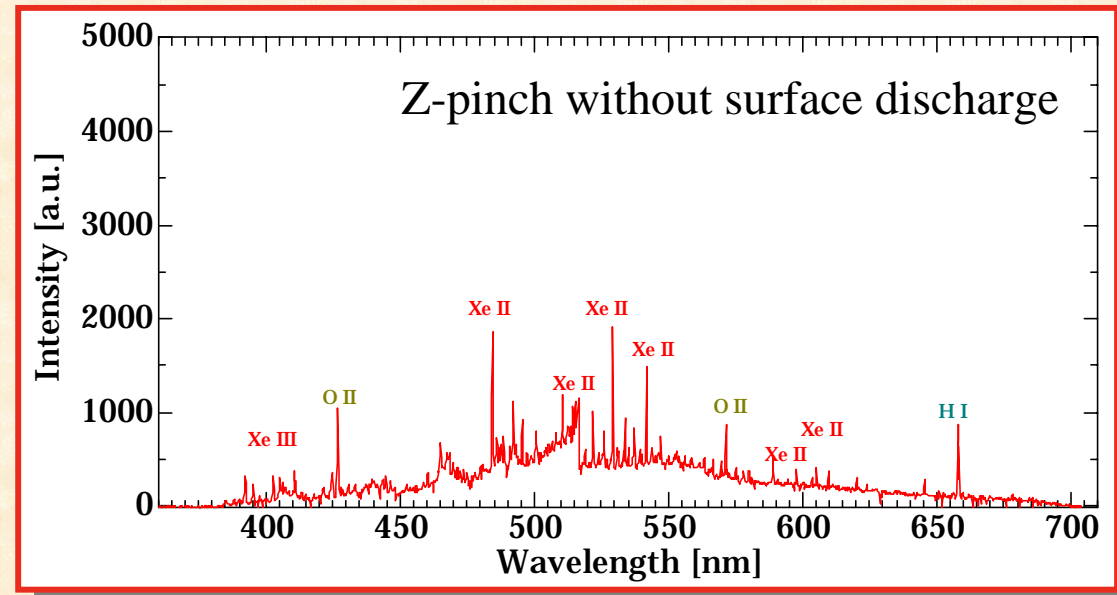
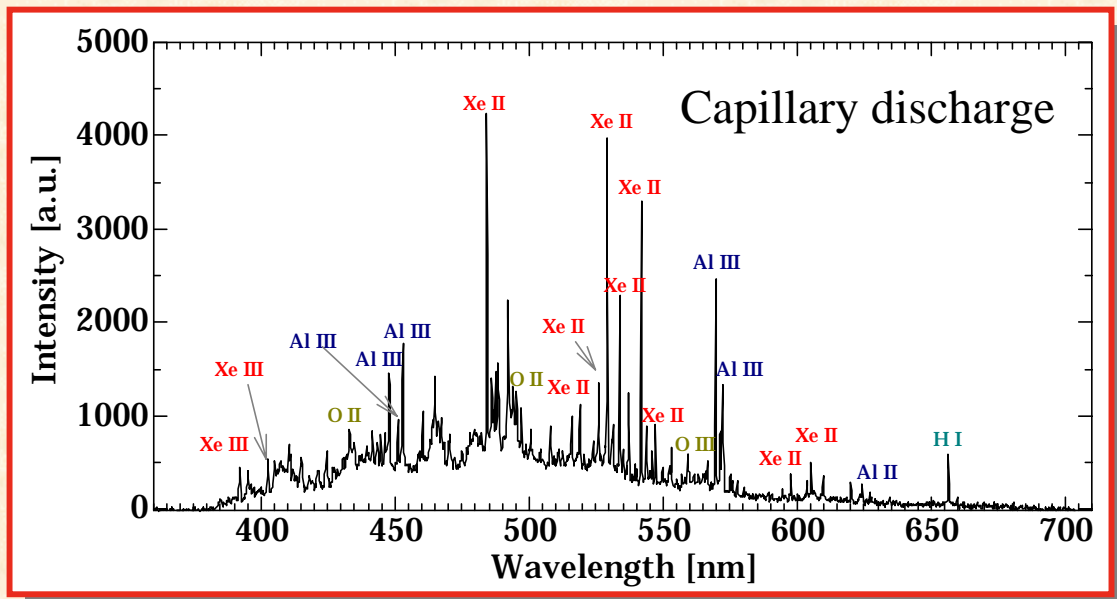
Pre-ionization by magnetic switch

Pinched

FWHM of pinch plasma = $330 \mu\text{m}$



Spectra with and without surface discharge



- ◆ Charging voltage $V_c = 9$ kV, Xe gas pressure $P = 4.5$ Torr
- ◆ Z-pinch without surface discharge shows low spectrum intensity in entire band
- ◆ Al impurity lines are disappeared

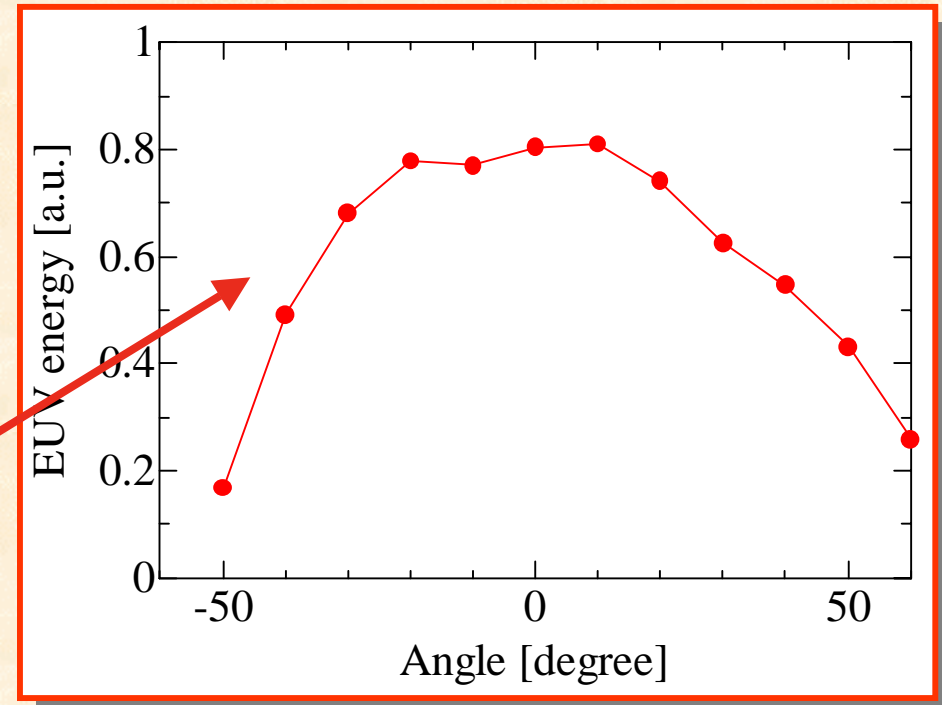
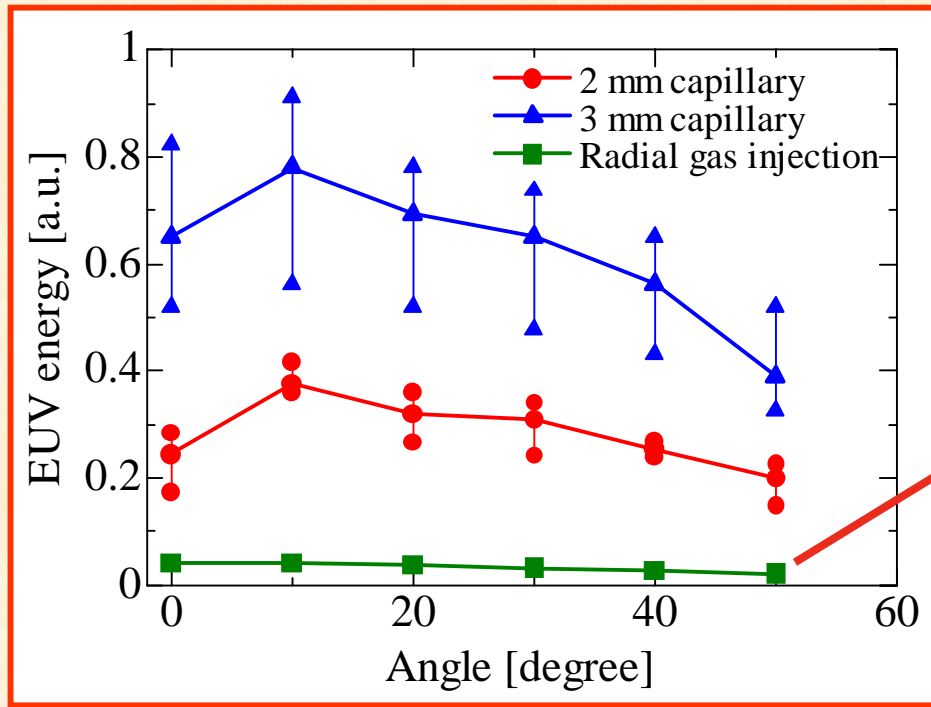


Really pinched plasma ?

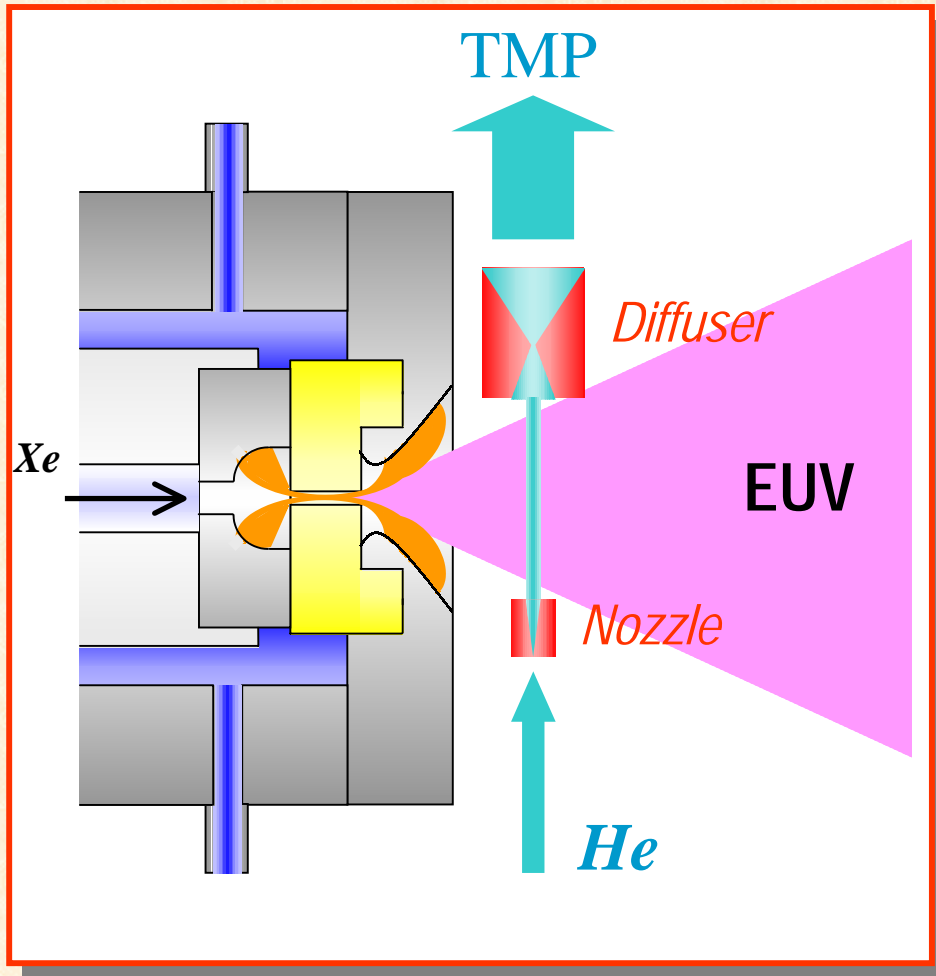
- ◆ Change the pre-ionization timing and value, discharge current



Angular distribution of EUV energy



- ◆ EUV energy of 3 mm capillary is higher than the 2 mm capillary
- ◆ Stability of 2 mm capillary is better than 3 mm capillary
- ◆ EUV energy of radial gas injection is lower than that of capillary
- ◆ Need the study of the pre-ionization of Z-pinch without surface discharge

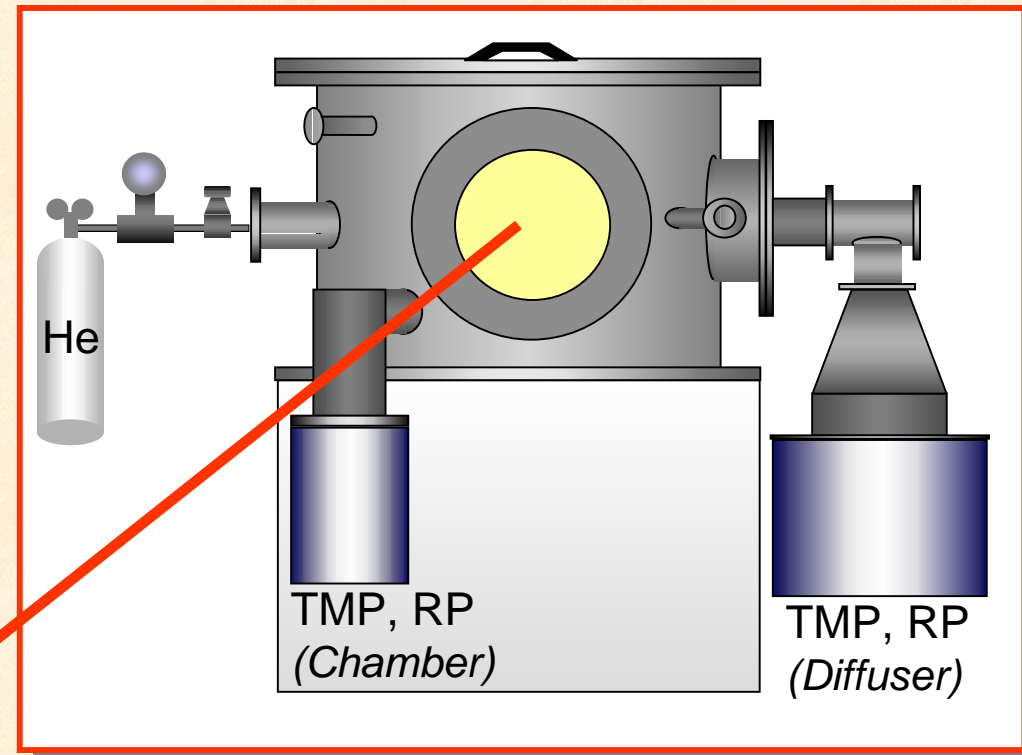
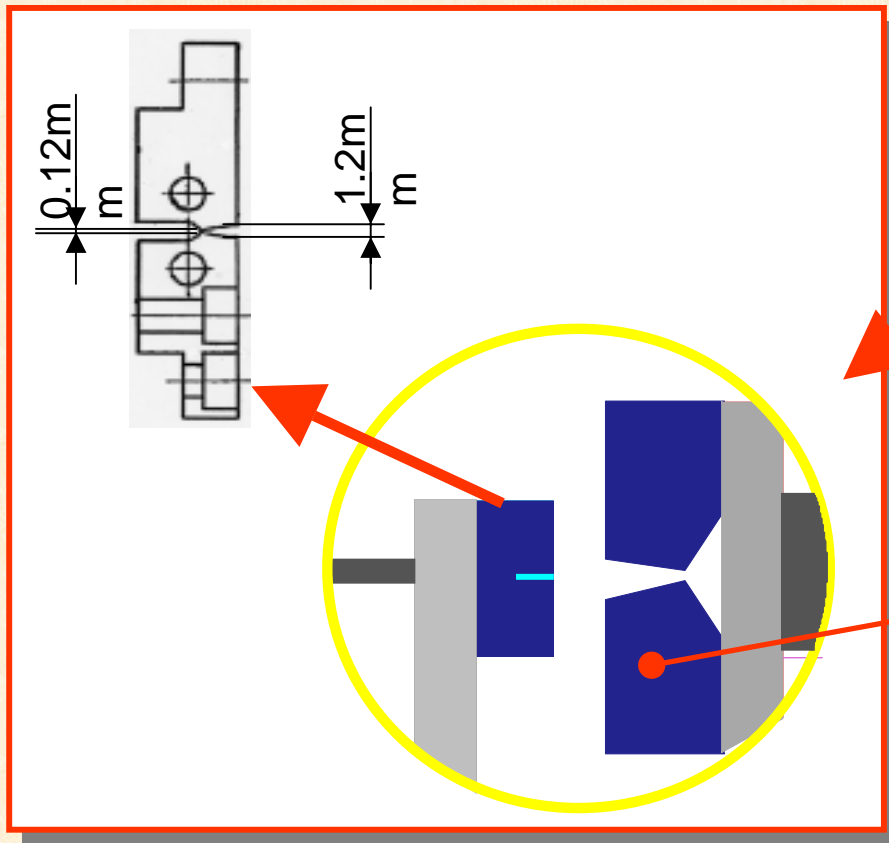


◆ Basic concept and characteristics

- Steady state operation
- Matching of pressure at outlet of nozzle
 - Stable discharge
 - Minimum caliber (smaller load)
- Slit type supersonic jet with high Mach number
- Nozzle with maximum expansion structure
 - Excellent optical performance

◆ Nozzle

- Hypersonic type
- Mach number ? 5
- Flow : width < 10 mm, thickness < 2 mm

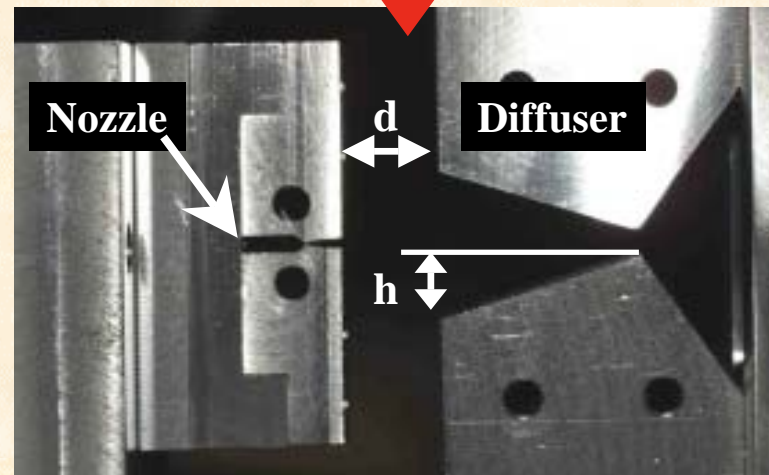


◆ Diffuser

- High efficient pressure recover
- Minimum influence on the background gas pressure



- ◆ Mach number : 5
- ◆ Nozzle and Diffuser
 - $d = 5 \sim 15$ mm
- ◆ Diffuser shapes
 - $h = 4, 6, 8$ & Throat width: 2-6 mm
- ◆ Now, Basic test is being conducted





◆ Conclusions

- The effect of discharge current dI/dt on EUV power and debris generation is observed
- New electrode is tested and will be improved
- Test bed of gas curtain has been constructed and find optimum design value

◆ Acknowledgment

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